

IN THE ABSTRACT OF THE DISCLOSURE:

Please replace the original abstract with the following new abstract:

ABSTRACT OF THE DISCLOSURE

An apparatus for plasma processing which has a vacuum vessel forming a plasma producing part, a gas supply for supplying a gas to the vacuum vessel, an antenna generating an electric field in the plasma producing part, a Faraday shield provided at an outer periphery of the vacuum vessel, a high-frequency electric source supplying a high-frequency electric power to the antenna and the Faraday shield, and an end point determinator and detector.